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UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 6,716,760 B2 DATED : April 6, 2004 Page 1 of 1

INVENTOR(S) : Young-Hun Bae et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title page, Item [54] and Column 1, line 5,

Title, please delete "AND" and insert -- AND AN --.

Title page.

Item [75], Inventors, please delete "Icheon" and replace with -- Gyunggi-do --; and delete "Pyungtaek" and replace with -- Gyunggi-do --.

Column 4.

Lines 10-12, please delete "depositing an etching prevention layer wherein the anti-reflection layer and the etching prevention layer are formed of different materials, on the resultant structure;" and replace with -- depositing an etching prevention layer on the resultant structure; --.

Lines 13-14, please delete "depositing an anti-reflection layer on the etching prevention layer;" and replace with -- depositing an anti-reflection layer on the etching prevention layer wherein the anti-reflection layer and the etching prevention layer are formed of different materials, --.

Lines 38-40, please delete "depositing an etching prevention layer wherein the antireflection layer and the etching prevention layer are formed of different materials, on the nitride layer," and replace with -- depositing an etching prevention layer on the nitride layer, --.

Lines 41-42, please delete "depositing an anti-reflection layer on the etching prevention layer," and replace with -- depositing an anti-reflection layer on the etching prevention layer wherein the anti-reflection layer and the etching prevention layer are formed of different materials, --.

Signed and Sealed this

Twenty-first Day of December, 2004

JON W. DUDAS
Director of the United States Patent and Trademark Office